L Number	Hits		DB	Time stamp
86	10	1 , , , , , , , , , , , , , , , , , , ,	USPAT;	2004/03/19 17:31
		or ("6376332") or ("6428620")).PN.	US-PGPUB;	
			EPO; JPO;	
			DERWENT; IBM TDB	
87	25	((belt near2 like) same (ring or polygon))	USPAT;	2004/03/19 17:34
07	23	same electrode	US-PGPUB;	2001,03,13 17.31
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
88	1514	(belt near2 like) same electrode	USPAT;	2004/03/19 17:34
		·	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
	207	/	IBM_TDB	2004/02/10 17 26
89	387	(anodize or anodizing) near substrate	USPAT; US-PGPUB;	2004/03/19 17:36
			EPO; JPO;	
			DERWENT;	
			IBM TDB	
90	l о	((belt near2 like) same electrode) and	USPAT;	2004/03/19 17:36
		((anodize or anodizing) near substrate)	US-PGPUB;	
		-	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
91	4479	,	USPAT;	2004/03/19 17:37
		electrode	US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM TDB	
92	٦	((anodize or anodizing) near substrate) and	USPAT;	2004/03/19 17:37
) Z		((first and second and third and fourth)	US-PGPUB;	2001, 03, 13 1, 13,
		near electrode)	EPO; JPO;	
		·	DERWENT;	
			IBM_TDB	
-	226	((205/323) or (205/199)).CCLS.	USPAT;	2004/03/18 16:28
			US-PGPUB;	
			EPO; JPO;	İ
			DERWENT; IBM TDB	
_	13636	anodize or anodizing	USPAT;	2004/03/18 16:29
	13030	anourse or anoursing	US-PGPUB;	2001, 03, 10 10.23
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	49	(((205/323) or (205/199)).CCLS.) and	USPAT;	2004/03/18 16:29
		(anodize or anodizing)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
_	1348243	electrode	USPAT:	2004/03/18 16:32
	1540243	010011040	US-PGPUB;	2004/05/10 10.52
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	31		USPAT;	2004/03/18 16:38
		(anodize or anodizing)) and electrode	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
	1.5	//HE056220H\ or /H5011240H\ or /H6100027H\	IBM_TDB	2004/02/19 36:41
-	15	(("5856229") or ("5811348") or ("6190937") or ("6221738") or ("6382292") or ("6143628")	USPAT	2004/03/18 16:41
		or ("6306729") or ("6331208") or ("6613678")		
		or ("6391743") or ("6211038") or ("6428620")		
		or ("6376332") or ("5565084") or		
		("6258698")).PN.		
-	3646500		USPAT;	2004/03/18 20:47
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
	L		IBM_TDB	

r · · · · · · · · · · · · · · · · · · ·	·		110DAM	2004/02/10 17 00
-	41465	electro near2 plating or electroless or	USPAT; US-PGPUB;	2004/03/18 17:09
		electro near2 deposition	EPO; JPO;	
			DERWENT;	
			IBM TDB	
-	524	(anodize or anodizing) and (electro near2	USPAT;	2004/03/18 17:09
		plating or electroless or electro near2	US-PGPUB;	
		deposition)	EPO; JPO;	
		-	DERWENT;	
			IBM_TDB	
-	244		USPAT;	2004/03/18 17:09
		plating or electroless or electro near2	US-PGPUB;	
		deposition)) and electrode	EPO; JPO;	
			DERWENT;	
	658264	first and second and third and fourth	IBM_TDB USPAT;	2004/03/18 17:10
_	050204	lifet and second and third and routen	US-PGPUB;	2004/03/18 17:10
			EPO; JPO;	
		'	DERWENT;	
			IBM TDB	
_	80	(((anodize or anodizing) and (electro near2	USPAT;	2004/03/18 17:11
		plating or electroless or electro near2	US-PGPUB;	,
	1	deposition)) and electrode ) and (first and	EPO; JPO;	
		second and third and fourth)	DERWENT;	
			IBM_TDB	
-	60	apparatus and ((((anodize or anodizing) and	USPAT;	2004/03/18 17:26
		(electro near2 plating or electroless or	US-PGPUB;	
		electro near2 deposition)) and electrode)	EPO; JPO;	
		and (first and second and third and fourth))	DERWENT;	
	627	(	IBM_TDB	2004/02/10 17 07
-	637	(anodize or anodizing) same apparatus	USPAT;	2004/03/18 17:27
			US-PGPUB; EPO; JPO;	
			DERWENT;	
			IBM TDB	
_	104298	(first and second and third and fourth) and	USPAT;	2004/03/18 19:32
		electrode	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	58		USPAT;	2004/03/18 19:29
		((first and second and third and fourth) and	US-PGPUB;	
		electrode )	EPO; JPO;	
			DERWENT; IBM TDB	
1_	138	((anodize or anodizing) same apparatus) same	USPAT;	2004/03/18 19:31
	130	substrate	US-PGPUB;	2001,03,10 13.31
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	387	(anodize or anodizing) near substrate	USPAT;	2004/03/18 19:31
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
	3222	(fings and gogand and thind and family)	IBM_TDB	2004/02/10 20 07
_	32230	(first and second and third and fourth) same electrode	USPAT; US-PGPUB;	2004/03/18 20:07
		erections	EPO; JPO;	
			DERWENT;	·
			IBM TDB	
_	8	((anodize or anodizing) near substrate) and	USPAT;	2004/03/18 19:33
		((first and second and third and fourth)	US-PGPUB;	
		same electrode )	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	1348243	electrode	USPAT;	2004/03/18 20:07
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
L	1	<u> </u>	IBM_TDB	L

46	((anodize or anodizing) near substrate) same	USPAT;	2004/03/19 17:35
	electrode	US-PGPUB;	
		EPO; JPO;	
		DERWENT;	
		IBM_TDB	
30006	canon adj kabushiki adj kaisha	USPAT;	2004/03/18 20:24
		US-PGPUB;	
		EPO; JPO;	
		, ,	
	l		
364			2004/03/18 20:24
	(canon adj kabushiki adj kaisha)	1 ' 1	
		1 ' 1	
2646500			2004/02/10 20 45
3646500	apparatus		2004/03/18 20:47
103	(((anodize or anodizing) near substrate) not	_	2004/03/18 20:47
103	3	1 ' 1	2004/03/18 20:47
		1 ' 1	
	abbaracas		
		1 ' 1	
		electrode  30006 canon adj kabushiki adj kaisha  ((anodize or anodizing) near substrate) not (canon adj kabushiki adj kaisha)  3646500 apparatus	electrode  US-PGPUB; EPO; JPO; DERWENT; IBM_TDB US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB;